

	Hits	Search Text	DBs
1	2	(integrat\$3 near5 circuit\$4) and (((layout near8 object) or pattttern\$4) same (mask\$3 or photomask or reticle)) and (project\$4 near9 lens) and (expos\$4 or illuminant\$4 or irradiat\$4 or imag\$3) and ((lens near5 (material or element)) same (RI or (refract\$3 near6 index))) and ((proximity\$4 near14 correct\$4) same (calculat\$4 or estimat\$4 or determin\$4) same ((lithograph\$4 near9 model) or (thin near9 film near9 (optics or calculat\$4 or model)) or (Maxwell near9 equation)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
2	2	(integrat\$3 near5 circuit\$4) and (((layout near8 object) or pattttern\$4) same (mask\$3 or photomask or reticle)) and (project\$4 near9 lens) and (expos\$4 or illuminant\$4 or irradiat\$4 or imag\$3) and ((lens near5 (material or element)) same (RI or (refract\$3 near6 index))) and ((proximity\$4 near14 correct\$4) same (calculat\$4 or estimat\$4 or determin\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
3	2	(integrat\$3 near5 circuit\$4) and (((layout near8 object) or pattttern\$4) same (mask\$3 or photomask or reticle)) and (project\$4 near9 lens) and (expos\$4 or illuminant\$4 or irradiat\$4 or imag\$3) and ((lens near5 (material or element)) same (RI or (refract\$3 near6 index)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
4	13	(integrat\$3 near5 circuit\$4) and (((layout near8 object) or patttern\$4) same (mask\$3 or photomask or reticle)) and (project\$4 near9 lens) and (expos\$4 or illuminant\$4 or irradiat\$4 or imag\$3) and (lens same (RI or (refract\$3 near6 index)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
5	10	(integrat\$3 near5 circuit\$4) and (((layout near8 object) or patttern\$4) same (mask\$3 or photomask or reticle)) and (project\$4 near9 lens) and (expos\$4 or illuminant\$4 or irradiat\$4 or imag\$3) and (lens same project\$4 same ((close near9 proximit\$4) or contact or vicinit\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
6	3	(integrat\$3 near5 circuit\$4) and (((layout near8 object) or patttern\$4) same (mask\$3 or photomask or reticle)) and ((project\$4 near9 lens) same ((close near9 proximit\$4) or contact or vicinit\$3) same (sample or substrate or wafer or photosensitive)) and (expos\$4 or illuminant\$4 or irradiat\$4 or imag\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
7	10	(integrat\$3 near5 circuit\$4) and (((layout near8 object) or patttern\$4) same (mask\$3 or photomask or reticle)) and ((project\$4 near9 lens) same ((close near9 proximit\$4) or contact or vicinit\$3)) and (expos\$4 or illuminant\$4 or irradiat\$4 or imag\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
8	3	(integrat\$3 near5 circuit\$4) and (((layout near8 object) or patttern\$4) same (mask\$3 or photomask or reticle)) and ((project\$4 near9 lens) same ((close near9 proximit\$4) or contact or vicinit\$3 or depress\$4 or touch\$3 or indent\$5) same (sample or substrate or wafer or photosensitive)) and (expos\$4 or illumiant\$4 or irradiat\$4 or imag\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
9	3	(((layout near8 object) or patttern\$4) same (mask\$3 or photomask or reticle)) and ((project\$4 near9 lens) same ((close near9 proximit\$4) or contact or vicinit\$3 or depress\$4 or touch\$3 or indent\$5) same (sample or substrate or wafer or photosensitive)) and (expos\$4 or illumiant\$4 or irradiat\$4 or imag\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
10	200	(integrat\$3 near5 circuit\$4) and (mask\$3 or photomask or reticle) and ((project\$4 near9 lens) same ((close near9 proximit\$4) or contact or depress\$4 or touch\$3 or indent\$6) same (sample or substrate or wafer or photosensitive)) and (expos\$4 or illumiant\$4 or irradiat\$4 or imag\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
11	13	(integrat\$3 near5 circuit\$4) and (mask\$3 or photomask or reticle) and ((project\$4 near9 lens) same ((close near9 proximit\$4) or contact or depress\$4 or touch\$3 or indent\$6) same (sample or substrate or wafer or photosensitive)) and (expos\$4 or illuminant\$4 or irradiat\$4 or imag\$3) and ((lens near5 (material or element)) same (RI or (refract\$3 near6 index)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
12	5	((("6778327") or ("20040027675") or ("20040240047") or ("5121256") or ("6522484"))).PN.	US-PGPUB; USPAT
13	2	(integrat\$3 near5 circuit\$4) and (mask\$3 or photomask or reticle) and ((project\$4 near9 lens) same ((close near9 proximit\$4) or contact or depress\$4 or touch\$3 or indent\$6) same (sample or substrate or wafer or photosensitive)) and (expos\$4 or illuminant\$4 or irradiat\$4 or imag\$3) and (solid near6 immersion near6 lens) and ((Maxwell near9 equation) or (proximity near9 correct\$4) or (thin near6 film near6 optics))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
14	2	(mask\$3 or photomask or reticle) and ((project\$4 near9 lens) same ((close near9 proximit\$4) or contact or depress\$4 or touch\$3 or indent\$6) same (sample or substrate or wafer or photosensitive)) and (expos\$4 or illuminant\$4 or irradiat\$4 or imag\$3) and (solid near6 immersion near6 lens) and ((Maxwell near9 equation) or (proximity near9 correct\$4) or (thin near6 film near6 optics))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
15	14	(mask\$3 or photomask or reticle) and (expos\$4 or illuminant\$4 or irradiat\$4 or imag\$3) and (solid near6 immersion near6 lens) and ((Maxwell near9 equation) or (proximity near9 correct\$4) or (thin near6 film near6 optics))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB